



D. Thin Film Process Technology **분과**

2019년 2월 14일(목), 11:00-12:30

Room F (실버홀, 5층)

**[TF2-D] 2-Dimensional Materials**

좌장: 안지훈 교수(한국해양대학교), 전우진 교수(경희대학교)

<p><b>TF2-D-1</b> 11:00-11:15</p>	<p><b>The Controllable Carrier Polarity of WSe<sub>2</sub> Field Effect Transistor Dependent on Contact Metal</b> Dain Kang, Taekwang Kim, Somyeong Shin, Hyewon Du, Minho Song, Seonyeong Kim, Hansung Kim, and Sunae Seo <i>Department of Physics, Sejong University</i></p>
<p><b>TF2-D-2</b> 11:15-11:45</p>	<p><b>[초청]</b> <b>New Perspectives in Atomic Layer Deposition Technique for 2D Material Thinfilm Deposition and Thinfilm Deposition on 2D Materials</b> Woojin Jeon <i>Department of Advanced Materials Engineering for Information and Electronics, Kyung Hee University</i></p>
<p><b>TF2-D-3</b> 11:45-12:00</p>	<p><b>Wafer Scale Growth of MoS<sub>2</sub>/GaN Heterostructure Using Metal-Organic Chemical Vapor Deposition for Optoelectronic Application</b> Juhun Lee, Hyunwoo Jang, Taemyung Kwak, and Okhyun Nam <i>Department of Nano-Optical Engineering, Korea Polytechnic University</i></p>
<p><b>TF2-D-4</b> 12:00-12:15</p>	<p><b>Wafer-Scale Monolayer MoS<sub>2</sub> Growth on SiO<sub>2</sub> Substrate Using Modified Atomic Layer Deposition Technique</b> Dae Hyun Kim<sup>1</sup>, Dae Woong Kim<sup>2</sup>, Tea Jun Seok<sup>2</sup>, Hyun Soo Jin<sup>2</sup>, Jae Chan Park<sup>2</sup>, and Tae Joo Park<sup>1,2</sup> <sup>1</sup><i>Department of Advanced Materials Engineering, Hanyang University</i>, <sup>2</sup><i>Department of Materials Science and Chemical Engineering, Hanyang University</i></p>
<p><b>TF2-D-5</b> 12:15-12:30</p>	<p><b>Wafer-Scale Growth of Single Phase SnS<sub>2</sub> by Atomic Layer Deposition</b> Jung Joon Pyeon<sup>1,2</sup>, In-Hwan Baek<sup>1,3,4</sup>, Taek-Mo Chung<sup>5</sup>, Jeong Hwan Han<sup>6</sup>, Chong-Yun Kang<sup>1,2</sup>, and Seong Keun Kim<sup>1</sup> <sup>1</sup><i>Center for Electronic Materials, KIST</i>, <sup>2</sup><i>KU-KIST Graduate School of Converging Science and Technology, Korea University</i>, <sup>3</sup><i>Department of Materials Science and Engineering, Seoul National University</i>, <sup>4</sup><i>Inter-University Semiconductor Research Center, Seoul National University</i>, <sup>5</sup><i>Division of Advanced Materials, KRICT</i>, <sup>6</sup><i>Department of Materials Science and Engineering, Seoul National University of Science and Technology</i></p>